## **AMENDMENTS TO THE SPECIFICATION:**

Please insert the following paragraph at page 1, after the title and before "BACKGROUND OF THE INVENTION":

This application is a divisional of copending Application No. 09/793,760, filed on February 27, 2001, the entire contents of which are incorporated by reference herein.

Please replace the paragraph beginning at page 2, line 1, with the following amended paragraph:

Usually, such Usually, such a negative image-recording material utilizes a recording system where radicals generated by light or heat are used as the initiator to generate a polymerization reaction for hardening the photosensitive layer of exposed portions to form an image portion. Because this negative image-forming material is inferior in image formability when compared to the positive which causes dissolution of the photosensitive layer by the exposure energy of an infrared laser, heat treatment is generally conducted before the development step in order to promote a hardening reaction by polymerization thereby forming a strong image portion.

Please replace the paragraph beginning at page 4, line 12, with the following amended paragraph:

An object of the present invention is to provide a planographic printing plate having a highly sensitive negative photosensitive layer capable of being written with an infrared laser. Another object of the present invention is to provide a positive planographic printing plate excellent in image-forming properties and superior in storage stability in that the coating

Attorney's Docket No. <u>003510-147</u>

properties and image-forming properties of a photosensitive layer are not lowerd lowered even

after long-term storage.

Please replace the paragraph beginning at page 22, line 15, with the following amended

paragraph:

In general formula (II), Ar<sup>11</sup> and Ar<sup>12</sup> independently represent an aryl group having 20 or

less carbon atoms which may have a substituent group. When this aryl group has a substituent

group, the substituent group is preferably a halogen atom, a nitro group, an alkyl group having

12 or less carbon atoms, an alkoxy group having 12 or less carbon atoms or an aryloxy

group having 12 or less carbon atoms. Z11- represents a counterion selected from the group

consisting of halogen ion, perchlorate ion, tetrafluoroborate ion, hexafluorophosphate ion, and

sulfonate ion, and it is preferably perchlorate ion, hexafluorophosphate ion or aryl sulfonate ion.

Please replace the paragraph beginning at page 23, line 7, with the following amended

paragraph:

In general formula (III), Ar<sup>21</sup> represents an aryl group having 20 or less carbon atoms

which may have a substituent group. Preferable examples of the substituent group include a

halogen atom, a nitro group, an alkyl group having 12 or less carbon atoms, an alkoxy group

having 12 or less carbon atoms, an aryloxy group having 12 or less carbon atoms, an alkyl

amino group having 12 or less carbon atoms, a dialkyl amino group having 12 or less carbon

atoms, an aryl amino group having 12 or less carbon atoms and a diaryl amino group having 12

or less carbon atoms.  $Z^{21}$  represents a counterion defined in the same way as  $Z^{11}$ .

- 3 -

Please replace the paragraph beginning at page 25, line 19, with the following amended paragraph:

As the monomers, the esters of aliphatic multivalent alcohols and unsaturated carboxylic acids include e.g. oligomers of acrylates such as ethylene glycol diacrylate, triethylene glycol diacrylate, 1,3-butane diol diacrylate, tetramethylene glycol diacrylate, propylene glycol diacrylate, neopentyl glycol diacrylate, trimethylol propane triacrylate, trimethylol propane tri(acryloyloxy propyl) ether, trimethylol ethane triacrylate, hexane diol diacrylate, 1,4-cyclohexane diol diacrylate, tetraethylene glycol diacrylate, pentaerythritol diacrylate, pentaerythritol triacrylate, pentaerythritol tetracrylate tetraacrylate, dipentaerythritol diacrylate, dipentaerythritol hexacrylate hexaacrylate, sorbitol triacrylate, sorbitol tetracrylate tetraacrylate, sorbitol pentaerylate pentaacrylate, sorbitol hexacrylate hexaacrylate, tri(acryloyloxy ethyl) isocyanurate, polyester acrylate etc.

Please replace the paragraph beginning at page 34, line 2, with the following amended paragraph:

Compounds having nitrogen-nitrogen bonds: It is considered that the nitrogen-nitrogen bonds are reductively cleaved to form active radicals. Specifically, hexaryl biimidazoles bisimidazoles can be preferably used.

Please replace the paragraph beginning at page 43, line 11, with the following amended paragraph:

The support is preferably a polyester film or an aluminum plate, of which the aluminum plate is excellent in dimensional stability and relatively inexpensive and is thus particularly

preferable. The aluminum plate is preferably a pure aluminum plate or an aluminium aluminum-based alloy plate containing a trace of different elements, or may be a plastic film having aluminum laminated or vapor-deposited thereon. The different elements contained in the aluminum alloy include silicon, iron, manganese, copper, magnesium, chromium, zinc, bismuth, nickel, titanium etc. The content of the different elements in the alloy is up to 10 % by weight. Aluminium Aluminum particularly preferable in the present invention is pure aluminum, but because production of absolutely pure aluminum is difficult in respect of refining techniques, aluminum may contain a trace of different elements. The composition of the aluminum plate thus used in the present invention is not limited, and any aluminum plates made of a known and conventionally used aluminum material can be used as necessary.

Please replace the paragraph beginning at page 57, line 6, with the following amended paragraph:

In the general formulae, X<sup>1</sup> and X<sup>2</sup> each represents -O- and -NR<sup>27</sup>. R<sup>21</sup> and R<sup>24</sup> each represents a hydrogen atom and -CH<sub>3</sub>. R<sup>22</sup>, R<sup>25</sup>, R<sup>29</sup>, R<sup>32</sup> and R<sup>36</sup> each represents analkylene an alkylene group havin having 1 to 12 carbon atoms, cycloalkylene group, arylene group and aralkylene group, which may have a substituent group. R<sup>23</sup>, R<sup>27</sup> and R<sup>33</sup> each represents a hydrogen atom, an alkyl group havin having 1 to 12 carbon atoms, cycloalkyl group, aryl group and aralkyl group, which may have a substituent group. R<sup>26</sup> and R<sup>37</sup> each represent an alkyl group having 1 to 12 carbon atoms, cycloalkyl group, and aralkyl group, which may have a substituent group, aryl group, and aralkyl group, which may have a substituent group. R<sup>28</sup>, R<sup>30</sup>, and R<sup>34</sup> represent a hydrogen atom and -CH<sub>3</sub>. R<sup>31</sup> and R<sup>35</sup> each represents an alkylene group having 1 to 12 carbon atoms, cycloalkylene group, arylene

group and aralkylene group, which may have a single bond or a substituent group.  $Y^{\dagger}$   $Y^{3}$  and  $Y^{2}$   $Y^{4}$  each represents a single bond and -CO-.

Please replace the paragraph beginning at page 60, line 4, with the following amended paragraph:

(4) Acrylamide, methacylamide methacrylamide and analogues thereof, such as N-methylol acrylamide, N-ethyl acrylamide, N-hexyl methacylamide methacrylamide, N-cylohexyl N-cyclohexyl acrylamide, N-hydroxyethyl acrylamide, N-phenyl acrylamide, N-nitrophenyl acrylamide, N-ethyl-N-phenyl acrylamide etc.

Please replace the paragraph beginning at page 66, line 15, with the following amended paragraph:

In the general formula (6) above, the anions represented by X- include e.g. perchloric acid, tetrafluoboric tetrafluoroboric acid, hexafluophosphoric hexafluorophosphoric acid, triisopropyl naphthalene sulfonic acid, 5-nitro-o-toluene sulfonic acid, 5-sulfosalicylic acid, 2,5-dimethyl benzene sulfonic acid, 2,4,6-trimethyl benzene sulfonic acid, 2-nitrobenzene sulfonic acid, 3-chlorobenzene sulfonic acid, 3-bromobenzene sulfonic acid, 2-fluorocapryl naphthalene sulfonic acid, dodecyl benzene sulfonic acid, 1-naphthol-5-sulfonic acid, 2-methoxy-4-hydroxy-5-benzoyl-benzene sulfonic acid, and p-toluene sulfonic acid. Among these, alkyl aromatic sulfonic acids such as hexafluophosphoric hexafluorophosphoric acid, triisopropyl naphthalene sulfonic acid and 2,5-dimethyl benzene sulfonic acid are particularly preferable. If anionic substituent groups are present on R<sup>1</sup> to R<sup>15</sup>, X may not be present.

Please replace the paragraph beginning at page 68, line 25, with the following amended paragraph:

Counter ions for the onium salts include tetrafluoboric tetrafluoroboric acid, hexafluophosphoric hexafluorophosphoric acid, triisopropyl naphthalene sulfonic acid, 5-nitro-o-toluene sulfonic acid, 5-sulfosalicylic acid, 2,5-dimethyl benzene sulfonic acid, 2,4,6-trimethyl benzene sulfonic acid, 2-nitrobenzene sulfonic acid, 3-chlorobenzene sulfonic acid, 3-bromobenzene sulfonic acid, 2-fluorocapryl naphthalene sulfonic acid, dodecyl benzene sulfonic acid, 1-naphthol-5-sulfonic acid, 2-methoxy-4-hydroxy-5-benzoyl-benzene sulfonic acid, and p-toluene sulfonic acid.

Please replace the paragraph beginning at page 69, line 8, with the following amended paragraph:

Among these, alkyl aromatic sulfonic acids such as hexafluophosphoric hexafluorophosphoric acid, triisopropyl naphthalene sulfonic acid and 2,5-dimethyl benzene sulfonic acid are particularly preferable.

Please replace the paragraph beginning at page 81, line 6, with the following amended paragraph:

Fluorine-type nonionic surfactant (Megafack Megafac F-177, Dainippon Ink and Chemicals,
Inc.)

Please replace the paragraph beginning at page 84, line 4, with the following amended paragraph:

Fluorine-type nonionic surfactant (Megafack Megafac F-177, Dainippon Ink and Chemicals,
Inc.)

Please replace the paragraph beginning at page 85, line 14, with the following amended paragraph:

• Monomer: a polymerizable compound (pentaerythritol tetracrylate tetraacrylate) 1.0 g

Please replace the paragraph beginning at page 85, line 18, with the following amended paragraph:

Fluorine-type nonionic surfactant (Megafack Megafac F-177, Dainippon Ink and Chemicals,
Inc.)

Please replace the paragraph beginning at page 89, line 19, with the following amended paragraph:

Fluorine-type surfactant (Megafack Megafac F-177, Dainippon Ink and
Chemicals, Inc.)

Please replace the paragraph beginning at page 94, line 14, with the following amended paragraph:

Fluorine-type surfactant (Megafack Megafac F-177, Dainippon Ink and
Chemicals, Inc.)